

(19) World Intellectual Property
Organization
International Bureau



(43) International Publication Date
6 January 2005 (06.01.2005)

PCT

(10) International Publication Number
WO 2005/000525 A1

(51) International Patent Classification⁷: **B24B 37/04**,
B24D 13/14

(21) International Application Number:
PCT/US2004/017493

(22) International Filing Date: 3 June 2004 (03.06.2004)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:
10/601,601 23 June 2003 (23.06.2003) US

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(81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

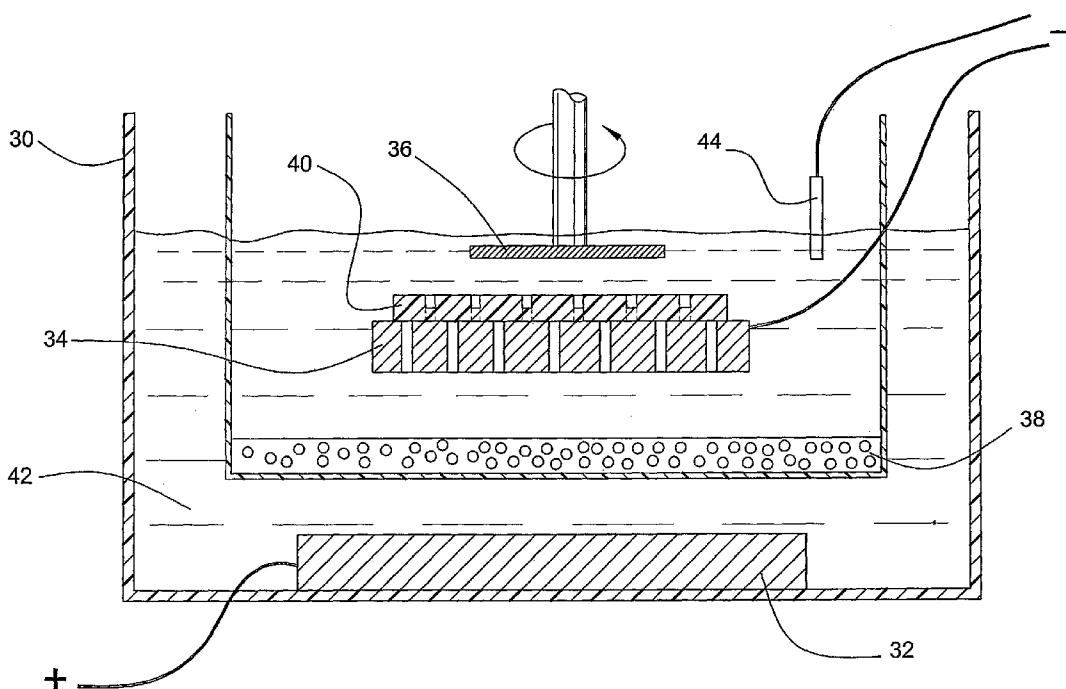
(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Declarations under Rule 4.17:

— as to applicant's entitlement to apply for and be granted a patent (Rule 4.17(ii)) for all designations

[Continued on next page]

(54) Title: POLISHING PAD FOR ELECTROCHEMICAL-MECHANICAL POLISHING



(57) Abstract: The invention provides a polishing pad comprising a body having a top surface (10) comprising a first set of grooves (12) with a first depth and first width and a bottom surface comprising a second set of grooves (16) with a second depth and second width, wherein the first set of grooves (12) and second set of grooves (16) are interconnected and are oriented such that they are not aligned.

WO 2005/000525 A1



- as to the applicant's entitlement to claim the priority of the earlier application (Rule 4.17(iii)) for all designations

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Published:

- with international search report